

Electronic Supplementary Information

Direct growth of ZnO crystals on various Cu substrates by Cu-catalyzed chemical bath deposition

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Experimental

Chemical bath deposition of ZnO. All aqueous solutions were prepared using reagent-grade chemicals and deionized (DI) water ($>10\text{ M}\Omega\text{ cm}$) purified by a Millipore Elix Advantage 5 system. As a pure Cu substrate, (i) a polycrystalline Cu plate for Hull cell tests ($67 \times 100 \times 0.3\text{ mm}$, surface roughness (R_a) = $\sim 20\text{ nm}$, Yamamoto-MS Co., Ltd.), (ii) a polished single-crystal Cu(111) plate ($10 \times 10 \times 0.5\text{ mm}$, $R_a < 3\text{ nm}$, MTI Co.) and (iii) a Cu mesh ($\phi 0.11 \times 100 \times 100\text{ mm}$, 100 mesh, Nilaco Co.) were used. First, substrates (i) and (iii) were cut to a size of $15\text{--}30 \times 50\text{ mm}$ as required. Prior to the deposition, these Cu substrates were cleaned by immersion in an alkaline degreasing solution (Ace Clean, Okuno Chemical Industries Co., Ltd.) at $50\text{ }^\circ\text{C}$ for 5 min and then rinsed with DI water. ZnO was deposited by the immersion of the Cu substrate in an aqueous solution containing $5.0\text{--}160\text{ mM Zn(NO}_3)_2 \cdot 6\text{H}_2\text{O}$ ($\geq 99\%$, Nacalai Tesque, Inc.) and 3 mM dimethylamine borane (DMAB, $\geq 97\%$, Wako Pure Chemical Industries, Ltd.) at $80\text{ }^\circ\text{C}$ for $0.5\text{--}1\text{ h}$ without agitation (the pH of the solution was ~ 5.8 at $25\text{ }^\circ\text{C}$). The deposits were rinsed with DI water and dried under ambient atmosphere.

Characterization of ZnO. The morphology and crystal structure of ZnO were examined by field-emission scanning electron microscopy (FESEM, JEOL JSM6700F) and X-ray diffraction using Cu $K\alpha$ radiation (XRD, Rigaku SmartLab). Photoluminescence (PL) spectra and Raman spectra were recorded on a microscopic laser Raman (PL) spectrometer (HORIBA LabRAM HR Evolution) using laser light with a wavelength of 325 nm and 532 nm , respectively.

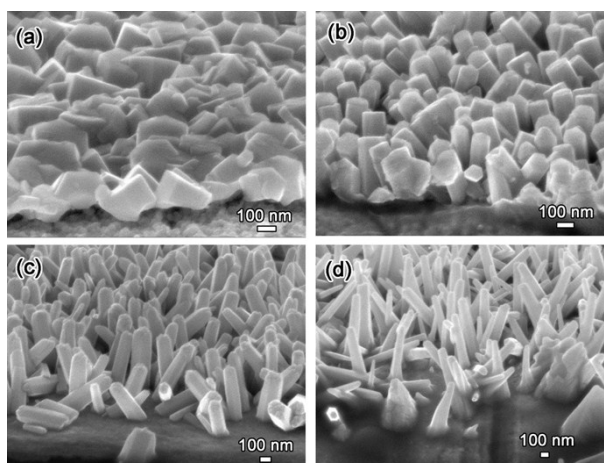


Figure S1. Tilt-view FESEM images of ZnO deposited on polycrystalline Cu plates by immersing in a $\text{Zn}(\text{NO}_3)_2$ -3 mM DMAB aqueous solution at 80 °C for 30 min at different $\text{Zn}(\text{NO}_3)_2$ concentrations: (a) 160, (b) 80, (c) 20 and (d) 5.0 mM.

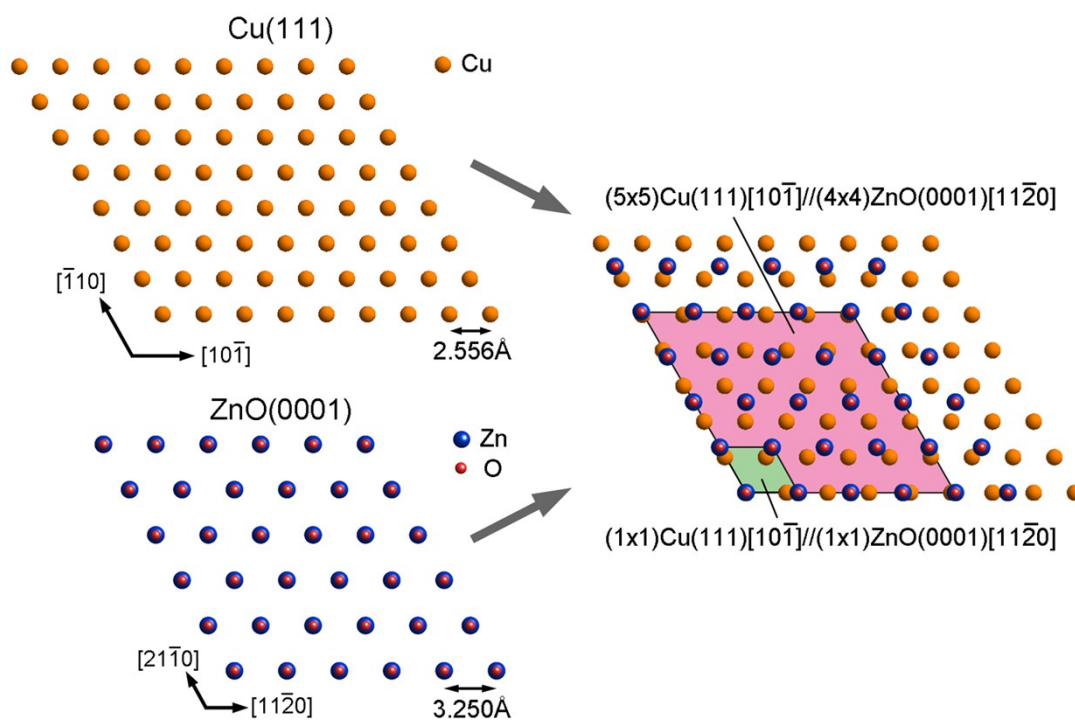


Figure S2. Schematic of the atomic arrangements for the Cu(111), ZnO(0001) planes and their overlap.

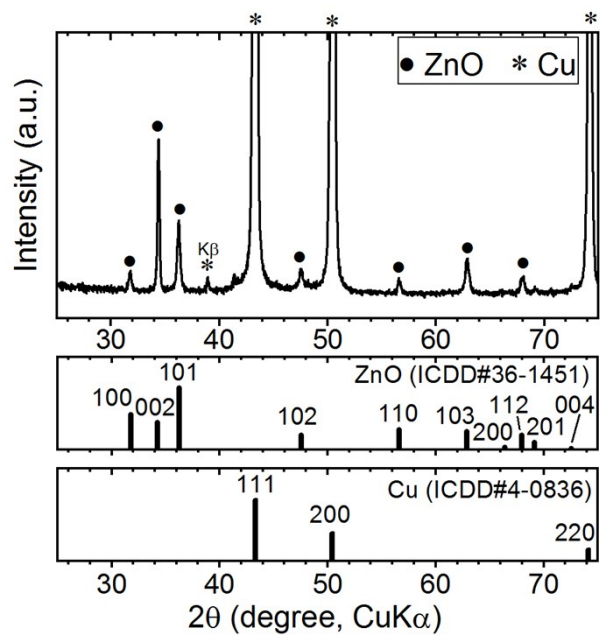


Figure S3. XRD pattern of ZnO obtained by immersing a Cu mesh in 5.0 mM $\text{Zn}(\text{NO}_3)_2$ –3.0 mM DMAB aqueous solution.